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PATENT

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Jeff Mackey

Serial No.: 10/715,955

Filed: November 18, 2003

For: POLARIZED RETICLE,
PHOTOLITHOGRAPHY SYSTEM, AND
METHOD OF FORMING A PATTERN
USING A POLARIZED RETICLE IN
CONJUNCTION WITH POLARIZED
LIGHT

Confirmation No.: 4444

Examiner: Unknown

Group Art Unit: 2872

Attorney Docket No.: 2269-6102US
(03-0857.00/US)

CERTIFICATE OF MAILING

I hereby certify that this correspondence along with any attachments referred to or identified as being attached or enclosed is being deposited with the United States Postal Service as First Class Mail on the date of deposit shown below with sufficient postage and in an envelope addressed to the Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

August 29, 2005
Date

Signature

Joseph A. Walkowski
Name (Type/Print)

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In compliance with the duty to disclose information material to patentability pursuant to 37 C.F.R. § 1.56, it is respectfully requested that this Supplemental Information Disclosure Statement be entered and the documents listed on attached PTO/SB/08 be considered by the Examiner and made of record. Copies of U.S. patents and U.S. patent publications are not being

submitted pursuant to M.P.E.P. 609 III A(2). Copies of foreign patent documents and non-patent literature are enclosed pursuant to 37 C.F.R. § 1.98(a)(2).

In accordance with 37 C.F.R. § 1.97(g) and (h), filing of this Supplemental Information Disclosure Statement is not to be construed as a representation that a search has been made or an admission that the information cited herein is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56(b). Further, no representation is made by Applicant herein that no other possible material information as defined in 37 C.F.R. § 1.56 (b) exists.

U.S. Patent Documents

<u>U.S. Patent No.</u>	<u>Publication Date</u>	<u>Patentee</u>
US - 5,673,103	09/30/1997	Inoue et al.
US - 2002/0197541 A1	12/26/2002	Grobman et al.

Foreign Patent Documents

<u>Document No.</u>	<u>Publication Date</u>	<u>Patentee</u>
JP 05241324	09/21/1993	Nikon Corp.
WO 02/44817 A2	06/06/2002	Wang et al.

Other Documents

International Search Report dated August 8, 2005 (4 pages).

WANG et al., "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design," Proceedings of SPIE, Vol. 4562, 2002, pp. 406-417.

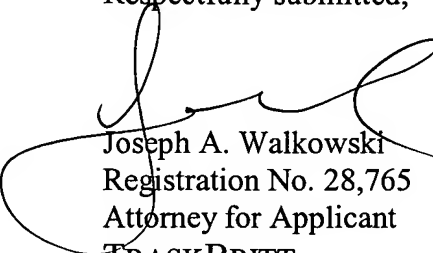
LAM et al, "Polarization masks: concept and initial assessment," Proceedings of SPIE, Vol. 4691, 2002, pp. 437-445.

BÖRNIG et al, "The Impact of Polarized Illumination on Imaging Characteristics in Optical Microlithography," Microelectronic Engineering, Elsevier Science B.V., Vol. 27, 1995, pp. 217-220.

Applicant offers to supply any explanation or discussion of the documents which the Examiner feels is necessary or desirable and which is requested.

This Supplemental Information Disclosure Statement is filed before the mailing date of a first Office Action on the merits.

Respectfully submitted,



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Date: August 29, 2005
JAW/ljb:slm

Enclosures: Form PTO/SB/08
Copy of foreign and non-patent documents cited

Document in ProLaw

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1

of

2

Complete if Known

Application Number

10/715,955

Filing Date

November 18, 2003

First Named Inventor

Jeff Mackey

Group Art Unit

2872

Examiner Name

Unknown

Attorney Docket Number

2269-6102US (03-0857.00/US)

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

**Examiner
Signature**

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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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2

of

2

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Application Number	10/715,955
Filing Date	November 18, 2003
First Named Inventor	Jeff Mackey
Group Art Unit	2872
Examiner Name	Unknown
Attorney Docket Number	2269-6102US (03-0857 00/US)

NON PATENT LITERATURE DOCUMENTS

Examiner Initials *	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		International Search Report dated August 8, 2005 (4 pages).	
		WANG et al., "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design," Proceedings of SPIE, Vol. 4562, 2002, pp. 406-417.	
		LAM et al, "Polarization masks: concept and initial assessment," Proceedings of SPIE, Vol. 4691, 2002, pp. 437-445.	
		BÖRNIG et al, "The Impact of Polarized Illumination on Imaging Characteristics in Optical Microlithography," Microelectronic Engineering, Elsevier Science B.V., Vol. 27, 1995, pp. 217-220.	

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